

ABSTRACT**[Abstract of the Disclosure]**

A metal-insulator-metal (MIM) capacitor is provided. The MIM capacitor
5 includes an upper electrode, a lower electrode, and a dielectric layer interposed
between the upper and lower electrodes. A first voltage is applied to the upper
electrode, and a second voltage is applied to the lower voltage. A wiring layer for
applying the first voltage to the upper electrode is formed on a lower level than or on the
same level as the lower electrode. Therefore, it is possible to minimize the thickness
10 of the dielectric layer as much as possible while maintaining the reliability of the
dielectric layer to some extent. Therefore, it is possible to realize a MIM capacitor
having a high capacitance.

[Representative Drawing]

15 FIG. 3

[Indexes]

MIM Capacitor, High Capacitance, Contact Hole